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	(FILE 'HOME' ENTERED AT 10:44:40 ON 22 MAR 2002)					
L1	FILE 'REGISTRY' ENTERED AT 10:44:47 ON 22 MAR 2002 413 (1 <ag<5 50<cu)="" and="" mac<="" td=""></ag<5>					
L2	11 L1 AND (0 <mg<.5 0<in<.5)="" mac<="" or="" td=""></mg<.5>					
т 2	FILE 'HCAPLUS' ENTERED AT 10:45:56 ON 22 MAR 2002					
L3	10 L2					
L4	102 ULTRAFINE (1A) WIRE					
L5	83797 (COPPER OR CU)(1A)(ALLOY OR BASE? OR REMAIN OR BALANC? OR REST)					
L6	20 L4 AND L5					
L7	530 L1					
F8	45 L7 AND WIRE?					

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AN
     1993-113024 [14]
                         WPIDS
DNC C1993-050294
     Bending-resistant, high strength conductive copper alloy
TI
     - contg. tin , silver and indium, for wire
     and crimped terminals.
DC
     L03 M26
PΑ
     (YAZA) YAZAKI CORP
CYC
     1
     JP 05051675 A 19930302 (199314)*
JP 2711949 B2 19980210 (199811)
PΙ
                                                 5p
                                                 5p
ADT
    JP 05051675 A JP 1991-208249 19910820; JP 2711949 B2 JP 1991-208249
     19910820
FDT JP 2711949 B2 Previous Publ. JP 05051675
PRAI JP 1991-208249 19910820
    JP 05051675 A UPAB: 19930924
     A Cu billet comprises (by wt.) Sn: 0.4-1.2%, Ag
     :0.1-1.0%, In: 0.1-0.8%, remainder Cu.
          USE/ADVANTAGE - Used for making conductive wire and
     crimp-style terminals without breaking of wire.
     0/0
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AN
     1991-311362 [43]
                        WPIDS -
DNN N1991-238566
                        DNC C1991-134879
     Copper alloy substrate of high temp. superconductive
ΤI
     layers - contains gallium, silver, zinc, indium,
     aluminium, manganese, magnesium, bismuth and/or beryllium.
DC
     L03 M26 U14 X12
IN
     ECKART, G; MULLER, R; ROHR, S
PA
     (DEAK) ZENT FESTK AKAD WIS
CYC
PΙ
     DD 290501
                  A 19910529 (199143)*
ADT DD 290501 A DD 1989-335941 19891220
PRAI DD 1989-335941
                     19891220
AΒ
          290501 A UPAB: 19930928
    A substrate material for high temp. superconductive layers consists of an
    alloy contg. (by wt.) 80-95% Cu and 5-20% total of one or more
     of Ga, Aq, Zn, In, Al, Mn, Mg, Bi and Be. Generally, the
    Cu alloy contains 5-20% total of Ga and upto 5%
    Aq, Zn, In, Al, Mn, Mg, Be or Bi.
         USE/ADVANTAGE - The substrate material is esp. useful for prodn. of
    magnetic screens and for wire or strip conductors for
     superconductive magnets, electrical machines and energy transmission
     cables. It is inexpensive, non-magnetic, workable and resistant at the
     superconductive layer heat treatment temp., to oxidn. and thermal cycling.
     It forms a good adherent base for the layers and has little or no
    deleterious affect on superconductive properties caused by chemical
     interaction and differential thermal expansion.
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0/0

1989-210150 [29] WPIDS DNC C1989-093251 DNN N1989-160153 ΤI Ultrafine copper alloy wire for winding contains chromium, at least one of zirconium, silver, tin and indium and balance copper. DC M26 V02 X12 (FURU) FURUKAWA ELECTRIC CO LTD PΑ CYC 1 PΙ JP 01147032 A 19890608 (198929)* 3p ADT JP 01147032 A JP 1987-304978 19871202 PRAI JP 1987-304978 19871202 JP 01147032 A UPAB: 19930923 AΒ Ultra-fine Cu alloy wire for winding comprises, by wt., 0.1 - 1.0% Cr, 0.05% at least one of Zr, Aq, Sn and In and balanced Cu. Pref. the wire has a dia. of up to 0.05 mm. USE - For winding wires. The solder dissolving resistance is improved by adding the alloying elements.

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1/1

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AN 1987-196552 [28] WPIDS DNN N1987-147048 DNC C1987-082359 Bonding wire for semiconductor device e.g. IC, LSI - comprises ΤI copper contg. sulphur matrix, and indium, magnesium, beryllium, boron, zirconium, silver, silicon, calcium etc.. DC L03 M26 U11 X12 (NIHA) NIPPON MINING CO; (TATD) TATSUTA DENSEN KK PΑ CYC 1 A 19870609 (198728)* PΙ JP 62127438 JP 03079416 B 19911218 (199203) JP 62127438 A JP 1985-265621 19851126; JP 03079416 B JP 1985-265621 ADT 19851126 PRAI JP 1985-265621 19851126 JP 62127438 A UPAB: 19930922 The bonding wire comprises Cu having 99.999 wt.% or over purity, contq. 0.0005 wt.% or less S, as a matrix, to which as additive elements, less than 0.02 wt.% (A) In and Mg, as a total, and 0.01 wt.% or less (B) at least one of Be, B, Zr, Y, Ag, Si, Ca, and rare earth elements, but 0.02 wt.% or less (A)+(B) groups, are added. USE - The bonding wire is used for connection between electrodes on semiconductor devices such as transistors, IC's, and LSI's, and outer leads. With the wire, heat resistance, fracture strength and bonding characteristics can be improved.

0/0

1986-166322 [26] WPIDS DNN N1986-123927 DNC C1986-071420 High purity copper wire for bonding semiconductor TI devices - contg. 5-50 ppm zirconium and/or niobium and 10-100 ppm palladium, silver, indium and tin. DC L03 M26 P55 (TANF) TANAKA DENSHI KOGYO KK PA CYC PΙ JP 61099646 A 19860517 (198626)* бр ADT JP 61099646 A JP 1984-221483 19841020 PRAI JP 1984-221483 19841020 AB JP 61099646 A UPAB: 19930922

Cu wire comprises (in wt.%) over 99.99 high purity Cu, and 5-150 ppm by wt. of one or more of 5-50 ppm Zr and Nb, and 10-100 ppm by wt. Pd, Ag, In, and Sn.

USE/ADVANTAGE - The wire is used for bonding tip electrodes of semiconductors and outer lead part and has the requisite (a) high tensile strength, (b) high strength at high temp., (c) hot press-bondability by plastic deformation, and supersonic bondability, (d) near true spherical ball shape, and consistency of shape, and (e) high bonding strength after bonding.

In an example, **Cu** wire comprising 3ppm Zr by wt. and balance 99.999% purity **Cu** was repeatedly wire drawn and process annealed to 25 micron dia.. It had a tensile strength of 10.6 gr, elongation of 25% at room temp., and tensile strength 9.9 gr, elongation of 18% at high temp., good ball shape, bonding strength 5.5 gr, hardness 43 Hv, and produced no fissures on Si-tips. 0/0

1982-46958E [23] AN WPIDS ΤI Heat- and corrosion-resistant copper alloy used in power transmission - contains silver and at least one of magnesium, aluminium, silicon, manganese, indium and rare earth metal. DC M26 PΑ (FURU) FURUKAWA ELECTRIC CO LTD CYC JP 57070244 A 19820430 (198223)* PΙ 3p PRAI JP 1980-144152 19801015 JP 57070244 A UPAB: 19930915 AΒ Copper alloy comprises 0.005-1.0% Ag, up to

2.0% in total of one or more elements selected from Mg, Al, Si, Mn, In, and rare earth metals and balance Cu.

The alloy is useful as a trolley wire for a distribution wire to be operated under a corrosive condition, instead of a conventional tough with correct The resistance of the

conventional tough pitch copper. The resistance of the copper alloy to heat and corrosive is improved by addn. of the controlled Ag amount. The Ag effect is further enhanced by the coexistence of Mg, Al, Si, etc.

1976-83733X [45] WPIDS AN Flexible electric conductor copper alloy - contg. TIcopper, zinc, magnesium and indium or silver.
L03 M26 X12 DC (FURU) FURUKAWA ELECTRIC CO LTD PΑ CYC PI, JP 50077215 A, 19750624 (197645) * PRAI JP 1973-127007 19731112 JP 50077215 A UPAB: 19930901 The Cu alloy contg. In 0.10-2.0, Mg 0.07-0.2, and In or Ag 0.10-1.0% is flexible and suitable for telephone wire and conductors for elec. blankets. In an example, Cu conductor alloy ingot contg. Zn 0.5, Mg 0.2, and In 0.2% was hot rolled to 10 mm. dia. at 800-850 degrees, and cold-drawn to 0.2 mm. dia. The props. were tensile strength is approx. 88 kg./mm2 and elec. cond. is approx. 58% IACS. The wire withstood is approx. 4.5 x 104 bend cycles.

AN 2001:777909 HCAPLUS

DN 135:321539

TI Copper alloy wire with high resistance to bending for electric cables

IN Matsui, Ryo; Ichikawa, Takaaki; Aoyama, Masayoshi; Setani, Osamu

PA Hitachi Cable, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 7 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 2001295011 A2 20011026 JP 2000-108017 20000405

AB A Cu-Ag, Cu-Nb, Cu-Fe, or Cu-Cr alloy wire is drawn to .ltoreq.0.1 mm and then heat treated to obtain a tensile strength of .gtoreq.450 MPa, an elongation of .gtoreq.4%, and an elec. cond. of .gtoreq.50% IACS. The preferred alloys are Cu-(1-15%) Ag, Cu-(5-20%)Nb, Cu-(5-20%)Fe, and Cu-(5-20%)Cr. The heat treatment is conducted by passing the wire inside a tubular furnace heated to .gtoreq.500.degree.. The wire is used for elec. cables.

AN 2000:486420 HCAPLUS

DN 133:93080

TI Cu-Ag alloy wire rods and their manufacture

IN Moriyasu, Takeshi; Tanaka, Akira; Hirota, Toru; Kumano, Tomoyuki; Ohgaki, Toshihisa

PA Showa Electric Wire and Cable Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 2000199042	A2	20000718	JP 1999-193434	19990707
PRAI	JP 1998-313577	А	19981104		
	JP 1998-313578	A	19981104		

AB The wire rods are manufd. by cold working cast rods of Cu-base alloys contg. 2-14 wt.% Ag and balance Cu for diam decrease, while heating them .gtoreq.1 times during working and cold working at area redn. .gtoreq.90%, preferably, .gtoreq.99%, after the final heat treatment. Alternatively, the wire rods are manufd. by heating the Cu-base alloys above for pptn., intermediate cold working, heating them for annealing and recovery, and final cold working at area redn. .gtoreq.90%, preferably, .gtoreq.99%. The wire rods have fibrous structures contg. Cu-base solid soln. phase, Cu-Ag eutectic phase, and Cu-Ag pptd. phase and tensile strength .gtoreq.1000 MPa. The wire rods show high strength, elec. cond., and bending resistance.

AN 1999:681605 HCAPLUS

DN 131:302273

- TI Manufacture of copper alloy thin wire having high strength and fatigue resistance
- IN Fujiwara, Hidemichi; Yamazaki, Akira; Osada, Katsuki
- PA Furukawa Electric Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 7 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PΤ

Cu alloy thin wire having diam. .ltoreq.50 .mu.m is from Cu-(1.0-4.5%)Ag alloy, Cu-(0.2-1.5%)Cr alloy, Cu-(0.1-0.3%)Zr alloy, Cu-(0.2-1.5)Cr-(0.1-0.3%)Zr alloy or Cu-(0.3-4.0%)Ti alloy by cold drawing at .ltoreq.99.999% draft optionally with intermediate annealing. When intermediate annealing is carried out, the cold draft between intermediate annealing processes is .ltoreq.99.999% and the cold draft after the final annealing is 80-99%.

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AN 1999:565493 HCAPLUS

DN 131:217697

TI Flexible wires and cables having durability and their manufacture

IN Miyake, Gyouichi; Takahara, Hidefusa; Rave, Diek

PA Yoshinogawa Densen K. K., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

JP 11242914 A2 19990907 JP 1998-43443 19980225

PI JP 11242914 A2 19990907 JP 1998-43443 19980225

The wires are Cr fiber-reinforced Cu composites comprising Cu matrix and in-situ formed fibrous Cr having max. diam. .ltoreq.2.5 .mu.m and av. diam. .ltoreq.1.0 .mu.m. Optionally, the wires also contain dispersions of Ag or Zr. Cu alloys contg. 1-25 wt.% Cr are swaged if necessary, cold drew, soln. treated, and cold drew again for in-situ formation of fibrous Cr to give wires, from which the flexible wires are manufd. The wires are further age-hardened for dispersion pptn. of Ag and Zr and in-situ formation of fibrous Cr when the Cu alloy contains 0.01-8 wt.% Ag or Zr. Cables contg. the sheathed wires and method for their manuf. are also claimed. The wires and the cables are esp. useful in industrial robot arms.

AN 1999:131049 HCAPLUS

DN 130:199625

- TI Copper alloys with high strength and high electric conductivity and manufacture of the alloy wires
- IN Ichikawa, Masateru; Kono, Osamu
- PA Fujikura Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 3 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 11050215 A2 19990223 JP 1997-210861 19970805

AB The alloys are prepd. by controlled cooling of cast Cu alloys contg. 0.1-0.45 wt.% O and 0.05-5 wt.% Ag at 3-100.degree./s cooling rate. The wires are manufd. by drawing the alloys. The wires are esp. useful as elec. cables.

AN 1995:275749 HCAPLUS

DN 122:139981

TI Manufacture of copper-silver alloys with high strength and high electric conductivity

IN Naoe, Kunihiro; Takayama, Teruyuki; Suzuki, Kazumoto

PA Fujikura Kk, Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 06287726 A2 19941011 JP 1993-74788 19930331

AB The Cu alloys are manufd. by hot working of Cu alloy ingots contg. 1-10% Ag and balance Cu at 570-680.degree., and cold working. During the cold working process (e.g., wire drawing), the Cu alloys are subject to heat treatment at 400-550.degree. in vacuum or inert-gas atm. for 0.5-40 h. The alloys have high strength and improved elec. cond.

AN 1994:287714 HCAPLUS

DN 120:287714

Plante in the state of

TI Multifilamentary niobium-titanium superconductive wire with high stability, strength, and processibility

IN Wada, Katsunori

PA Furukawa Electric Co Ltd, Japan

Jpn. Kokai Tokkyo Koho, 6 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 06005130 A2 19940114 JP 1992-184419 19920618

AB In the title superconductive wire useful for superconductor magnets, a part or the whole of a conductive metal matrix, in which a large no. of NbTi filaments are inserted, is a Cu-(0.1-5) wt.% Ag alloy. The Cu-Ag alloy may be put only in the periphery of the NbTi filaments. The superconductive wire may consist of a large no. of the NbTi filaments and the Cu-Ag alloy buried in a Cu-Ni alloy matrix.

AN. 1973:482656 HCAPLUS

DN 79:82656

TI Silver-containing copper wires with good tensile strength

IN Chiba, Hideo

PA Fujikura Cable Works, Ltd.

SO Japan. Kokai, 3 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
				<u>-</u>	
ΡI	JP 48044798	A2	19730627	JP 1971-33493	19710517
	JP 51034371	В4	19760925		

AB A 2.0-2.8:97.2-98 Ag-Cu alloy is cold drawn at least twice to 80-90% redn. in cross sectional area and annealed after each drawing. The product has good mech. strength and is useful in submarine cables. Thus, an ingot of 2.5:97.5 Ag-Cu was rolled to a 19-mm rod, heated at 680-770.degree., drawn to 8-mm-diam., annealed 3 hr at 360-80.degree., drawn to 3.2-mm diam., annealed 3 hr at 330.degree., and drawn to 0.65-mm diam. to give a wire with tensile strength 95.0 kg/mm2 and cond. 81.6%, compared with 75.0 and 83.4, resp., for a similarly drawn wire without annealing.

AN 2000:258837 HCAPLUS

DN 132:268491

TI Copper alloy wires having high conductivity and flexibility and their manufacture

IN Takahara, Hidefusa; Suzuki, Teruo; Matsuyama, Hiroaki; Kobayashi, Shigeru

PA Mitsui Mining and Smelting Co., Ltd., Japan; Yoshinogawa Densen K. K.

SO Jpn. Kokai Tokkyo Koho, 6 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

JP 2000113731 A2 20000421 JP 1998-285191 19981007

PI JP 2000113731 A2 20000421 JP 1998-285191 19981007

AB In manuf of Cu matrix composite contg in situ-formed Cr reinfo

AB In manuf. of Cu matrix composite contg. in situ-formed Cr reinforcement fiber, Ni plating is formed on the wire matrix and heat treated for .ltoreq.30 min at 900-980.degree. in H atm. or in vacuum, in the middle of the manufg. process. Wires having Cu

-Ni alloy surface layers, formed by diffusion of Ni and Cu, are also claimed. The wires are esp. useful as robot cables.

Wires having excellent solderability and Cu color tone are manufd.

AN 1992:617938 HCAPLUS

DN 117:217938

TI Copper alloy lead frames for semiconductor devices

IN Takemura, Masatoshi; Matsui, Toru; Abe, Hajime; Kato, Hiroshi

PA Hitachi Cable, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 04165055 A2 19920610 JP 1990-291449 19901029

AB The lead frames for direct bonding to Cu, Au, or Al lead wire without plating are prepd. by cold rolling at .gtoreq.80% a Cu alloy contg. 0.01-0.2% Zr and .ltoreq.10 ppm O. The Cu alloy may also contain 0.01-1.0 wt.% Sn, Fe, P, Cr, Ni, Co, Zn, Si, Mg, Ti, Te, and Ag. Thus, a lead frame of Cu-0.1% Zr had tensile strength 52.0 kg/mm2, elongation 8%, and good bondability.

1992:617938 HCAPLUS ΑN

117:217938 DN

Copper alloy lead frames for semiconductor devices TI

Takemura, Masatoshi; Matsui, Toru; Abe, Hajime; Kato, Hiroshi IN

Hitachi Cable, Ltd., Japan PA

Jpn. Kokai Tokkyo Koho, 4 pp. SO CODEN: JKXXAF

DTPatent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE JP 04165055 A2 19920610 JP 1990-291449 19901029

PΙ

AΒ The lead frames for direct bonding to Cu, Au, or Al lead wire without plating are prepd. by cold rolling at .gtoreq.80% a Cu alloy contg. 0.01-0.2% Zr and .ltoreq.10 ppm O. The Cu alloy may also contain 0.01-1.0 wt. % Sn, Fe, P, Cr, Ni, Co, Zn, Si, Mg, Ti, Te, and Ag. Thus, a lead frame of Cu-0.1% Zr had tensile strength 52.0 kg/mm2, elongation 8%, and good bondability.

AN 2001:388976 HCAPLUS

DN 134:374827

TI Ultrafine highly pure copper alloy wire and manufacture of the wire for electric wire

IN Matsui, Hakaru; Ichikawa, Takaaki; Tamura, Koichi; Aoyama, Masayoshi; Setani, Osamu; Okada, Ryohei

PA Hitachi Cable, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 8 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PΙ

PATENT NO. KIND DATE APPLICATION NO. DATE

JP 2001148206 A2 20010529 JP 1999-330012 19991119

AB The wire is made of an alloy of Cu contg. .ltoreq.1 ppm inevitable impurities as the matrix and 0.05-0.9 wt.% Sn, In, Ag, Sb, Mg, Al, and/or B, which is drawn to .ltoreq.0.08 mm final diam. and annealed. Alternatively, the wire is made of the above wire as a core, which is plated with Sn, Ag, Ni, Sn-Pb solder, or Pb-free Cu-Sn-Bi- or Cu-Sn-Ag-based solder. A carbon-based crucible for melting and a carbon-based mold for casting are used in the manuf. of the wire for redn. of the amts. of impurities. An elec. wire made of twisted above wires are also claimed, which is suitable for electronic devices.

AN 2000:393156 HCAPLUS

DN 133:33346

TI Copper-zirconium alloy wire and its manufacture

IN Matsui, Hakaru; Aoyama, Masayoshi; Ichikawa, Takaaki; Tamura, Koichi; Sekida, Katsuo; Konishi, Kenji

PA Hitachi Cable, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 2000160311 A2 20000613 JP 1998-334124 19981125

AB The title Cu alloy wire contains 0.01-0.20 wt.% Zr and has tensile strength .gtoreq.40 kgf/mm2, elongation .gtoreq.5%, elec. cond. .gtoreq.80% IACS, and wire diam. 0.02-0.10 mm. The wire is manufd. by the following steps: (1) heating a cast Cu alloy contg. 0.01-0.50 wt.% Zr at .gtoreq.950.degree. for .gtoreq.30 min for soln. treatment, (2) drawing and twisting the resulting ultrafine wire, and (3) aging the twisted wire by elec. heating at 10-20 V for 0.3-4.0 s for pptn. of Cu-Zr compds. Adhesion between the wires under the aging process can be prevented.

1997:783949 HCAPLUS AN 128:38193 DN Manufacture of copper (alloy) ultra-fine wires TΙ Ichikawa, Masamitsu; Ajimura, Shoji IN PΑ Fujikura Ltd., Japan Jpn. Kokai Tokkyo Koho, 3 pp. SO CODEN: JKXXAF DTPatent Japanese LΑ FAN.CNT 1 PATENT NO. KIND DATE APPLICATION NO. DATE _____ --------------JP 09314219 A2 19971209 JP 1996-135303 PΙ 19960529

AB The title Cu (alloy) wires are manufd. by cooling
Cu (alloy) wires with diam. .ltoreq.0.2 mm at
-196-0.degree. and wire drawing. The manufg. process prevents Cu
(alloy) wires from cracking and deformation.

AN 1991:169433 HCAPLUS

DN 114:169433

TI Coated copper alloy for ultra-fine wire

IN Kurosaka, Akito; Tominaga, Haruo; Tomomatsu, Kazuhiko; Aoyanagi, Mamoru

PA Fujikura Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

AB The wire core of the **Cu alloy** contg. 0.003-0.012% Zr and .ltoreq.10 ppm O is coated with the **Cu alloy** contg. 0.05-0.3% Ag and .ltoreq.10 ppm O for a coating/core cross-sectional area ratio of 40-60% for high rupturing strength and elongation for use in magnetic heads.

AN 1991:169432 HCAPLUS

DN 114:169432

TI Coated copper alloy for ultra-fine wire

IN Kurosaka, Akito; Tominaga, Haruo; Tomomatsu, Kazuhiko; Aoyanagi, Mamoru

PA Fujikura Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
		,			
PI	JP 02267811	A2	19901101	JP 1989-89925	19890410
	JP 06044412	В4	19940608		

AB The wire core from the **Cu alloy** contg. 0.05-0.3% Ag, 0.003-0.01% Zr, and .ltoreq.10 ppm O is coated with .gtoreq.99.99% Cu for the coating/core cross-sectional area ratio of .ltoreq.40% for rupturing resistance for use in magnetic heads.

AN 1990:29159 HCAPLUS

DN 112:29159

TI Copper alloy conductor for ultrafine wires

IN Doi, Seiichi; Okuno, Michio; Kaneko, Hideo

PA Furukawa Electric Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 3 pp. CODEN: JKXXAF

DT Patent

LA. Japanese

FAN.CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 01147032 A2 19890608 JP 1987-304978 19871202

AB The title conductor comprises 0.1-1.0 wt.% Cr; 0.05-0.5 wt.% Zr, Ag, Sn, and/or In; and balance Cu. The alloy was rolled, coated with polyurethane, and drawn to give elec. conductive wire with excellent solder-wettability.